

Microplasma-based synthesis of nanostructured Pt

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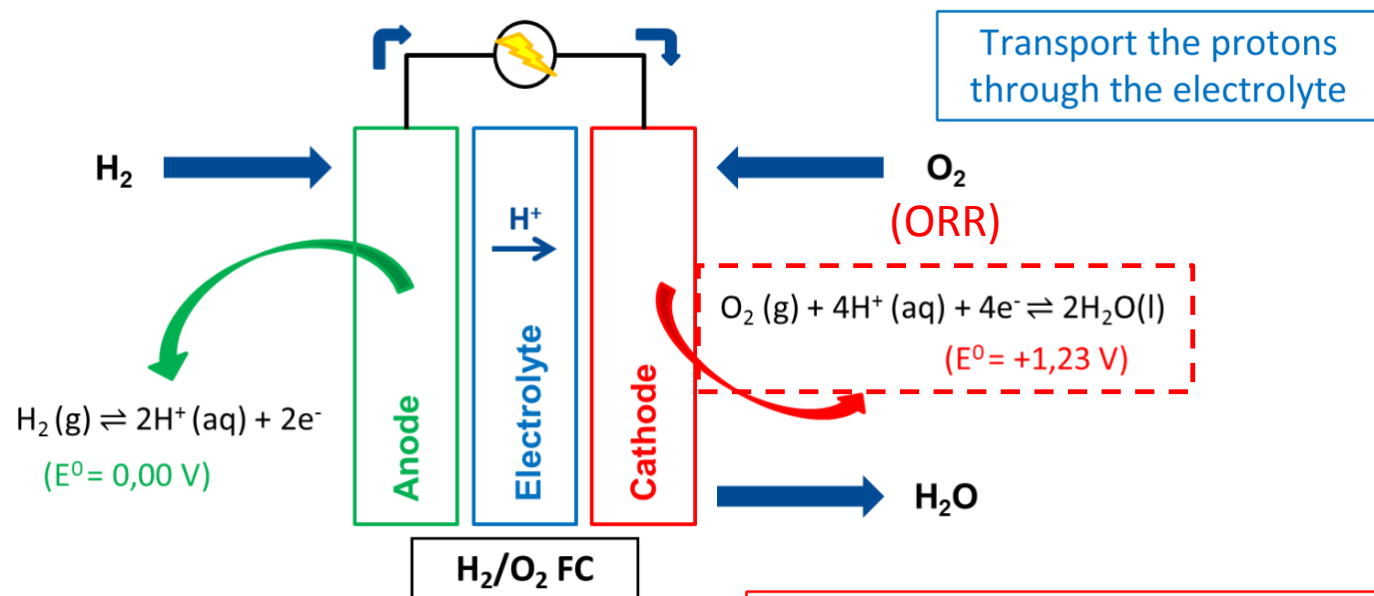
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Nanostructured Pt Films for H₂ based Fuel Cell



Net reaction (the "redox" reaction):
 $2\text{H}_2 + \text{O}_2 \Rightarrow 2\text{H}_2\text{O}$
 $E^0 = +1.23\text{V}$

Catalyze the reactions at the electrodes (especially at the cathode)

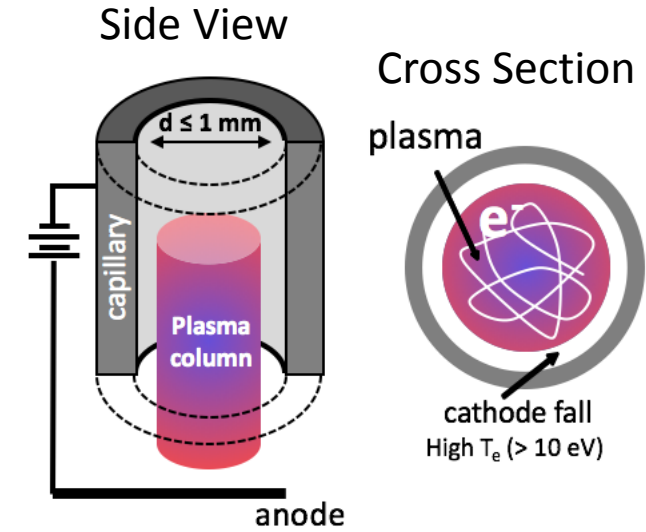
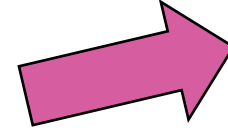
- Fuel Cell: Produces electricity through electrochemical reaction
- $2\text{H}_2 + \text{O}_2 \rightarrow 2\text{H}_2\text{O}$
- Fuel cells rely on Pt as a catalyst for oxygen reduction reaction (ORR)
- Platinum is an **expensive** metal → Use Pt more efficiently → Increase surface area, alloy Pt with other metals

Project Goals

- Utilize novel methods to deposit Pt nanoparticles for fuel cell catalysts → *microplasmas*
- Explore how plasma operating parameters affect Pt deposition:
 - Pressure
 - Pt-precursor Flux
 - Substrate type
 - Electrical configuration
- Characterize Pt films and nanoparticle morphology
- Investigate if Pt can alloyed with Ni
 - Can PtNi be deposited directly and is PtNi catalytically active for ORR?

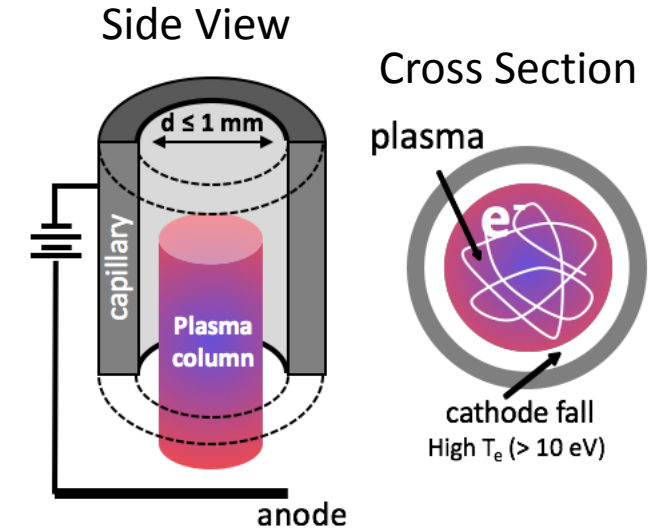
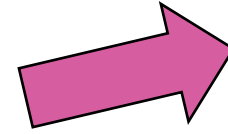
What is a microplasma?

- Dense plasma confined to very small space $\rightarrow 10\ \mu\text{m} - 1\ \text{mm}$



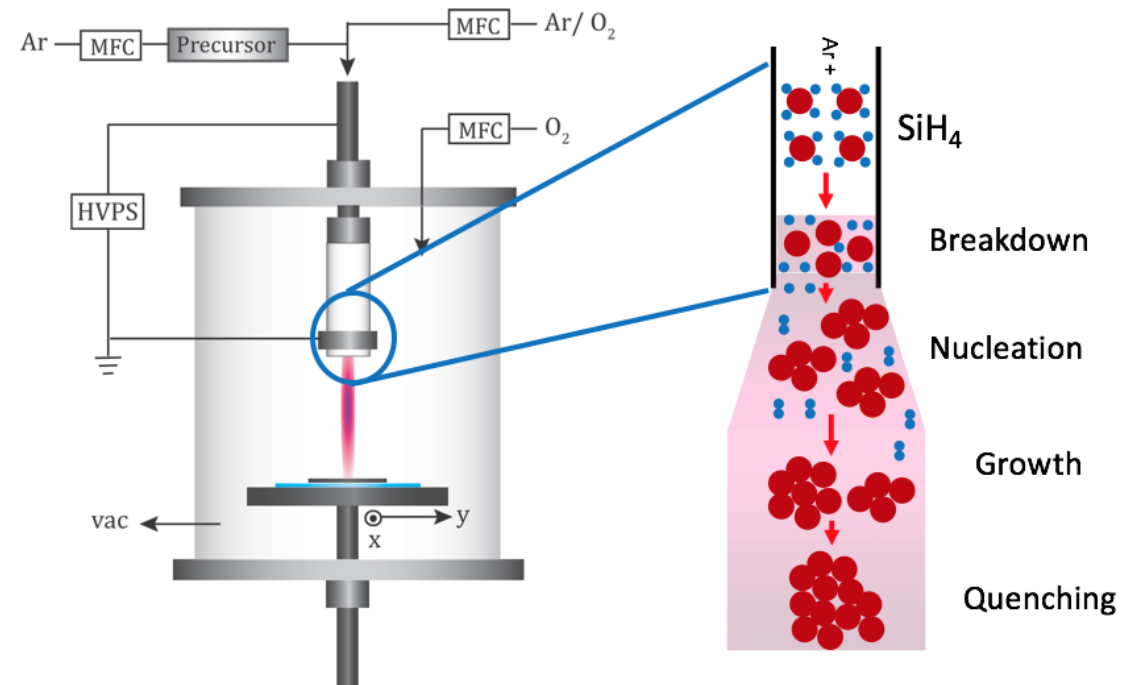
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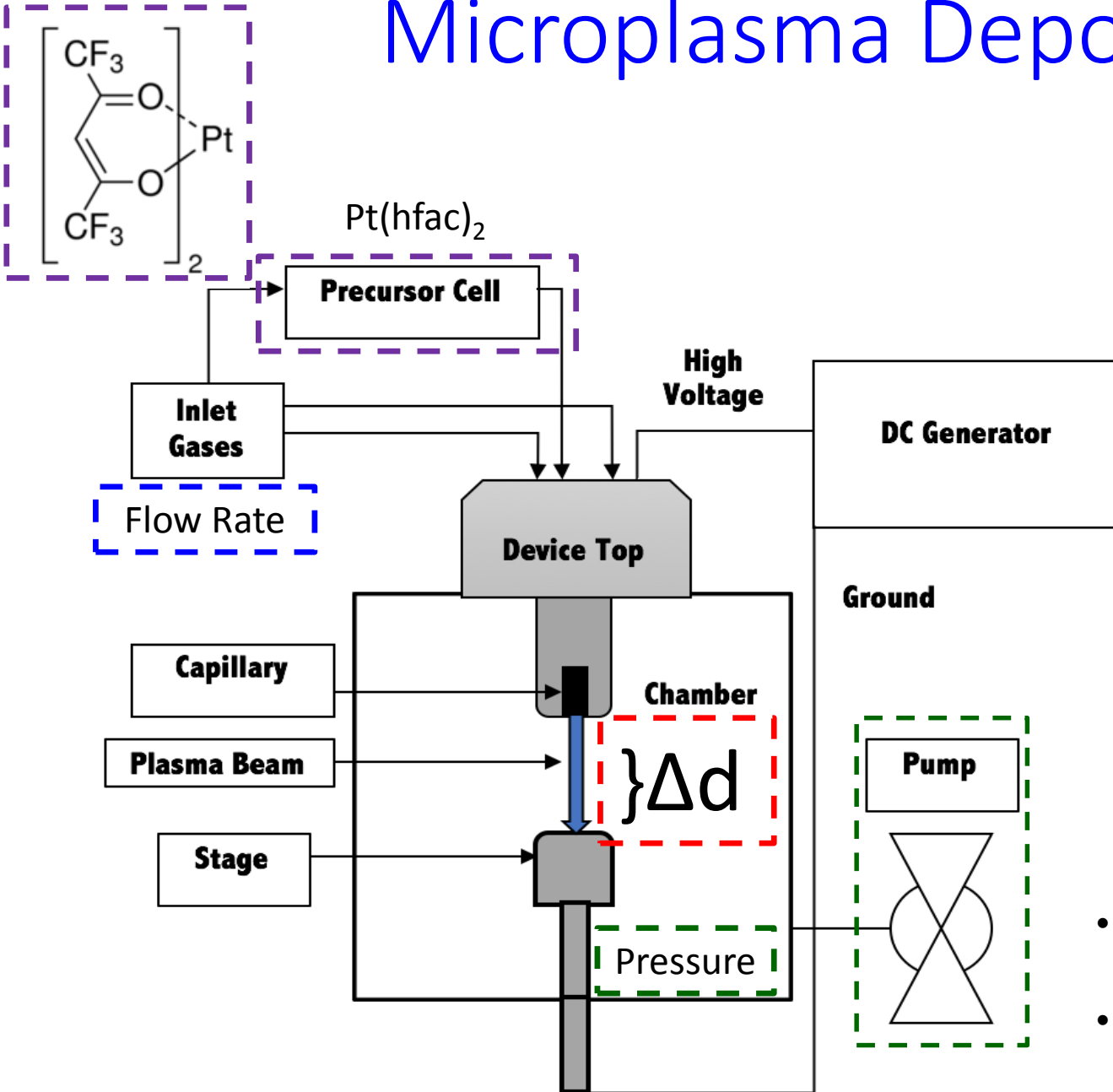


- Advantages

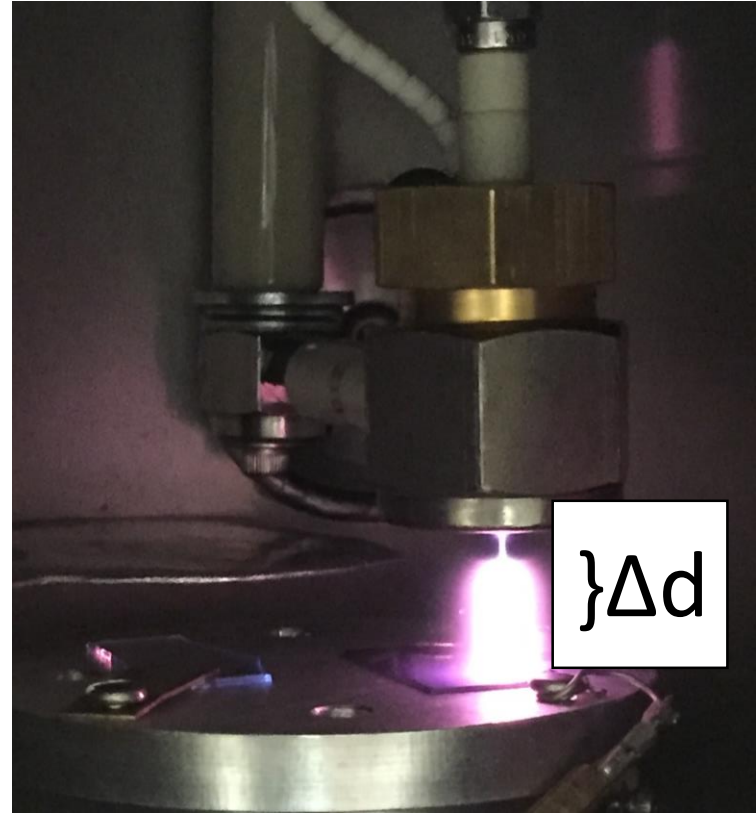
- Spray deposit nanostructured materials on any substrate
- Grow particles to nano/micro structured sizes
- Tune particle composition \rightarrow make alloys



Microplasma Deposition Reactor



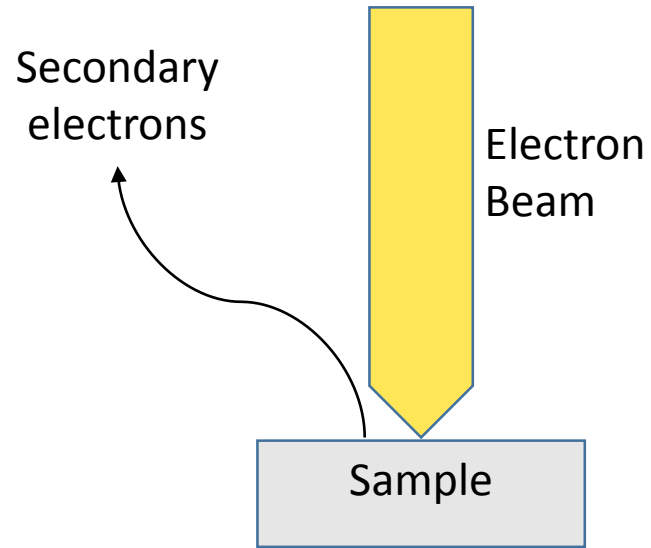
Pressure = 50 torr



- High voltage (plasma) discharge struck between capillary and substrate
- **Control Parameters:** gas flow rate, pressure, precursor, capillary-stage distance, cell temperature (for sublimation)

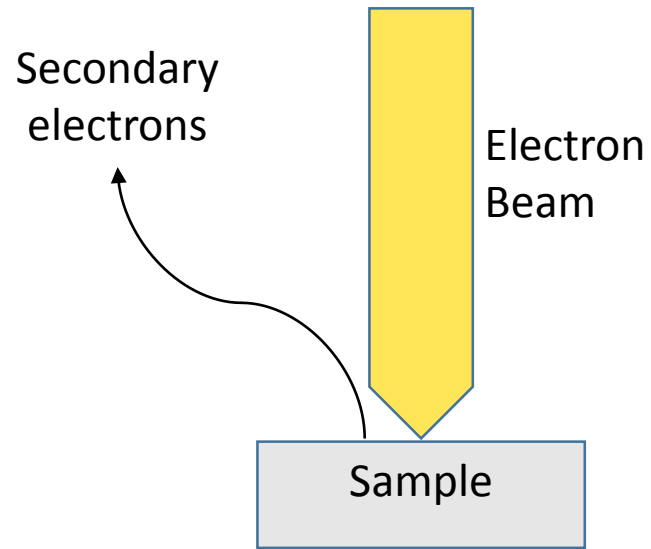
Characterization of Samples

Scanning Electron Microscope (**SEM**)
Morphology & thickness

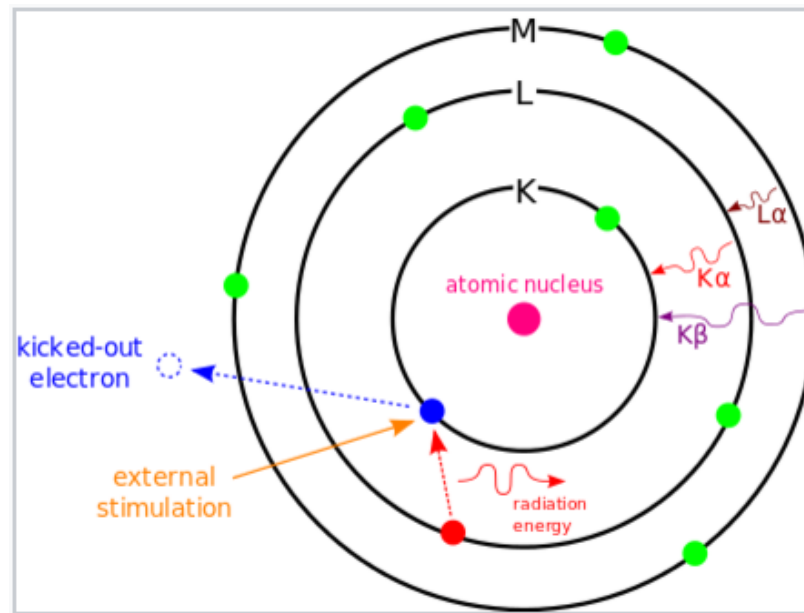


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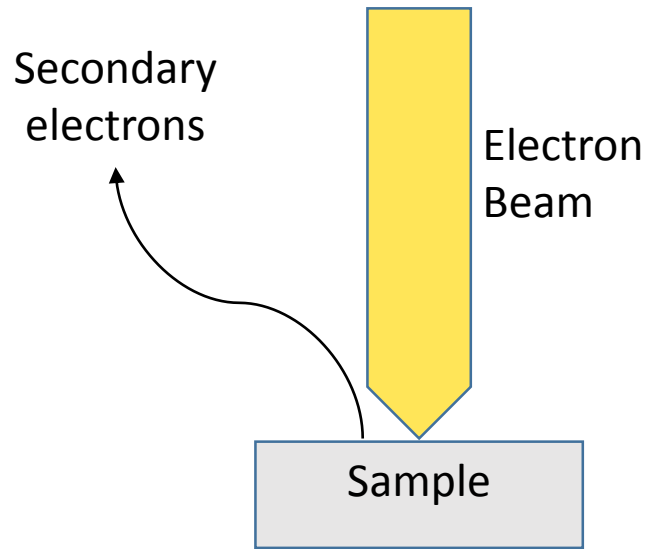


Energy Dispersive X-ray (**EDX**)
Film elemental composition

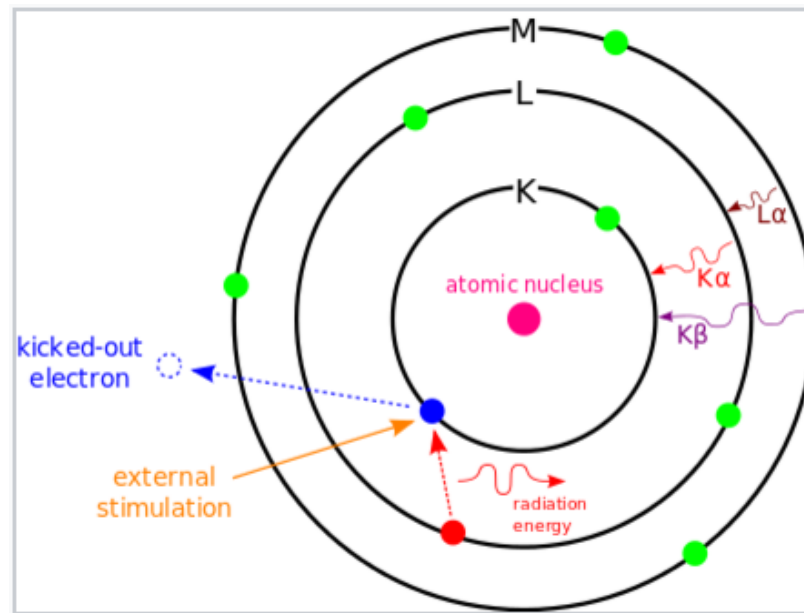


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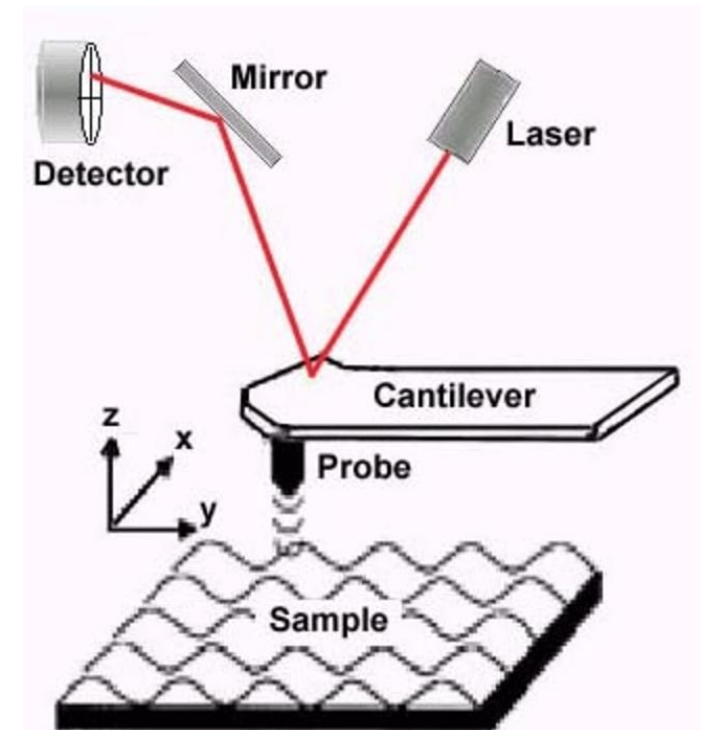
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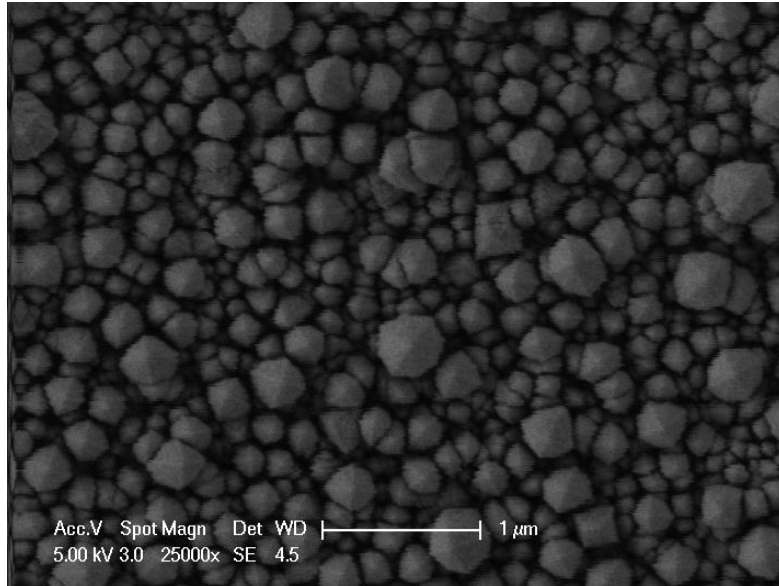


Atomic Force Microscope (**AFM**)
Surface topography

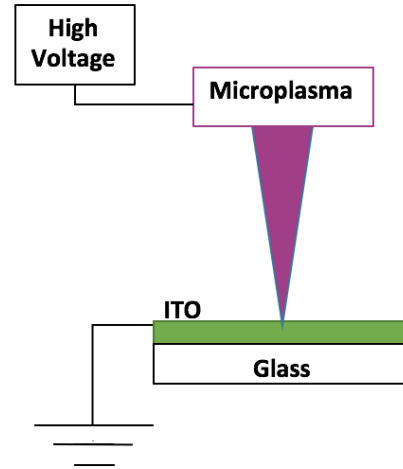


Pt film morphology: Substrate Effect at P = 760 torr

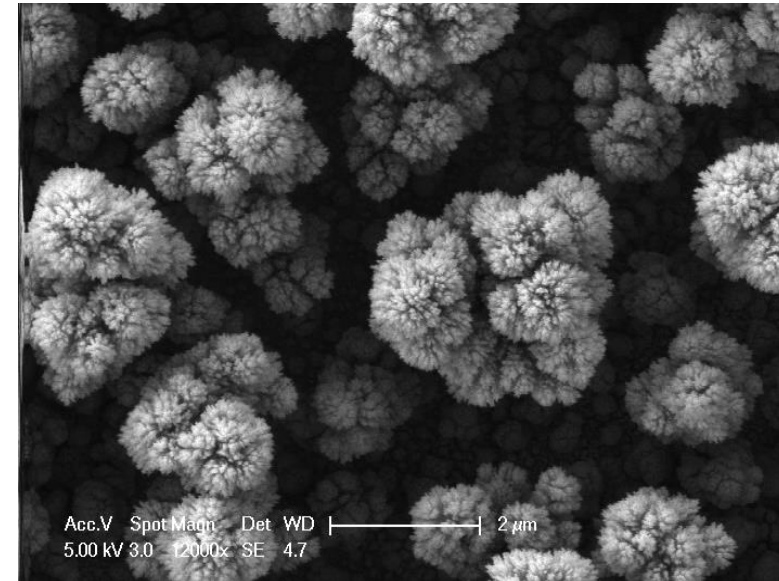
Substrate: **Indium Tin Oxide (ITO)**



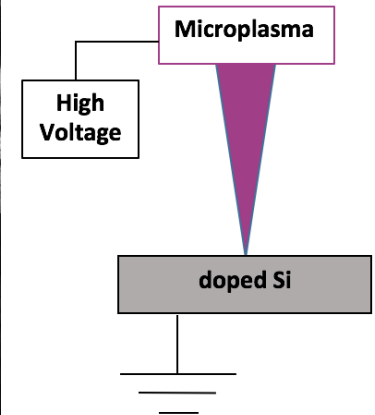
crystal facets → fcc Pt



Substrate: **Doped Silicon(Si)**



Porous deposit, 'ballistic' aggregation

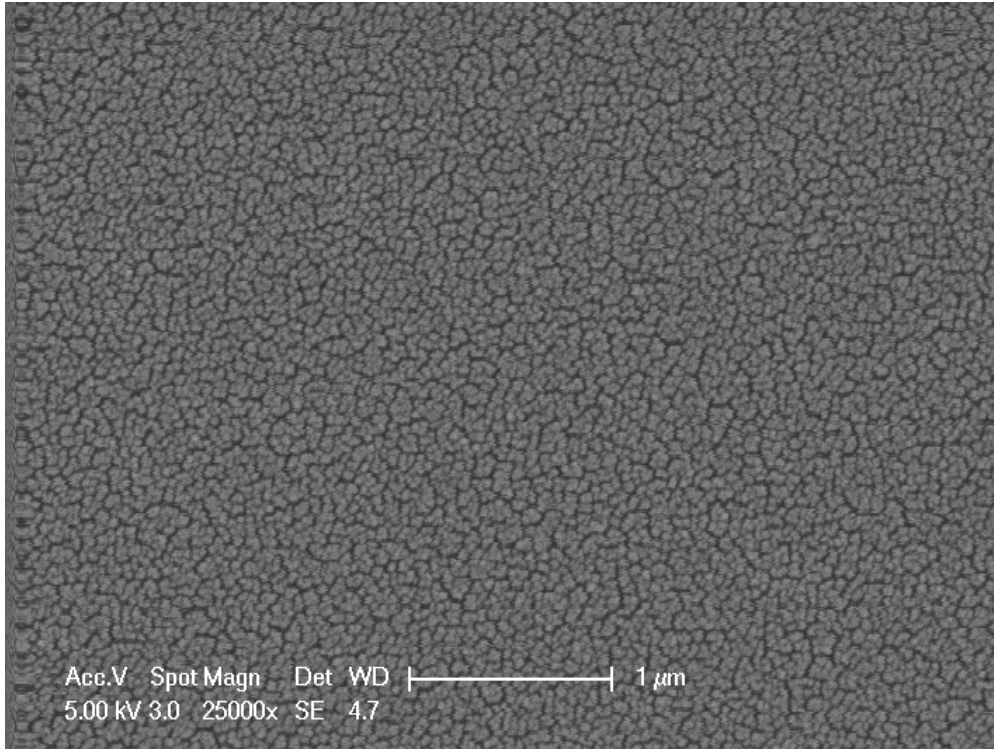


- Substrate type affects morphology
- How plasma current travels to ground affects morphology (thin ITO film vs. Si subst)

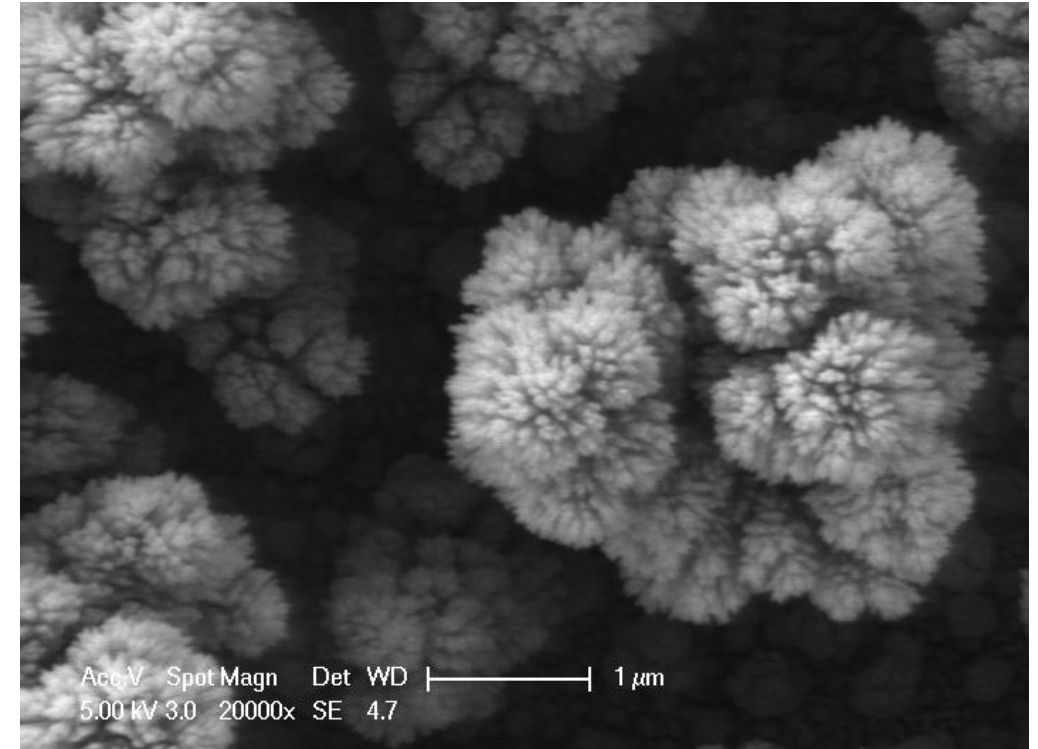
Control: P = 760 torr,
t = 30 min,
 $T_{Pt} = 45^{\circ}C$
 $\Delta d = 3$ mm

Pt film morphology: Pressure Effects

P = 50 torr



P = 760 torr (atm pressure)

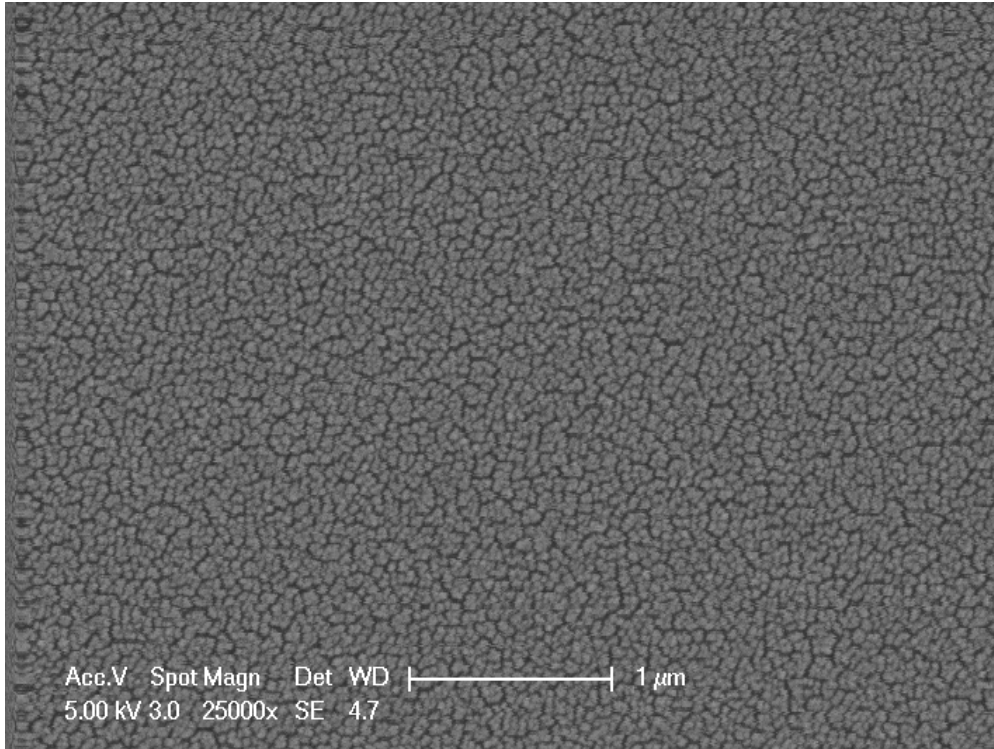


- Pressure significantly affects deposition process and film morphology
- Lower pressure = **lower Pt-precursor flux** → thinner film
- Higher pressure → ballistic-like aggregation of 'clusters', more porous

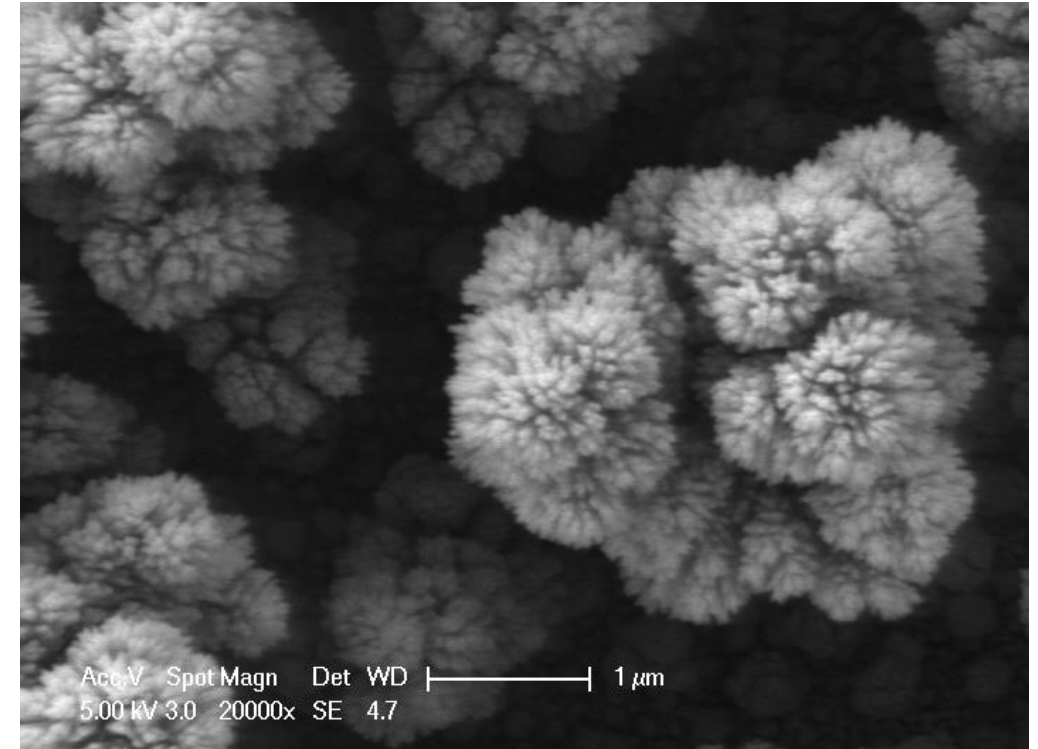
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Substrate: Si,
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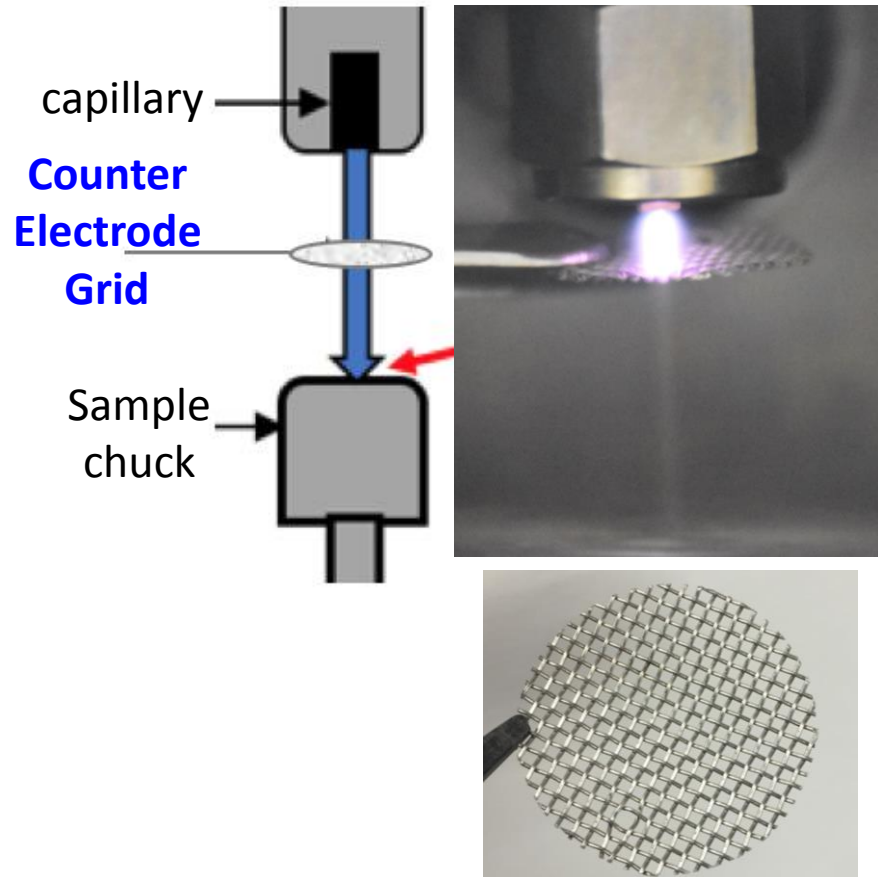


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- **Jet-substrate distance too small → move farther away + new counter-electrode**

Control:
Substrate: Si,
t = 30 min,
 $T_{Pt} = 45^{\circ}C$
 $\Delta d = 3$ mm

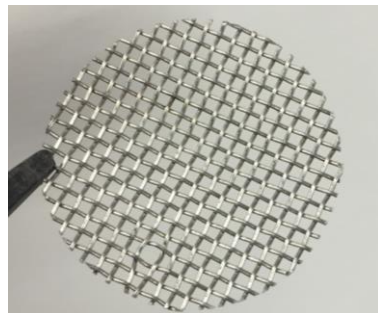
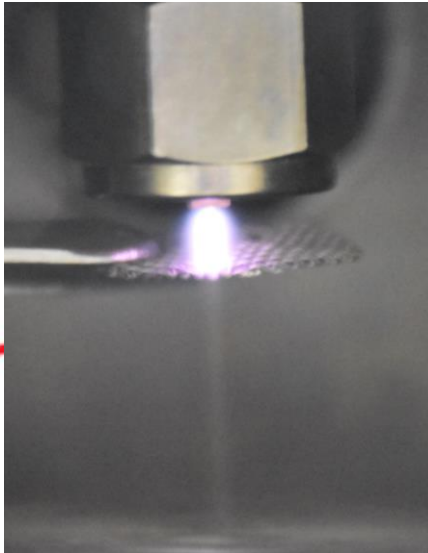
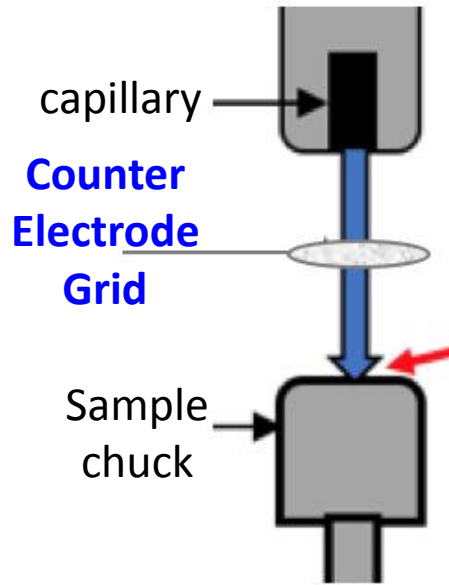
Pt Nanoparticle Deposition

- Larger capillary substrate distance needed → **New counter electrode**

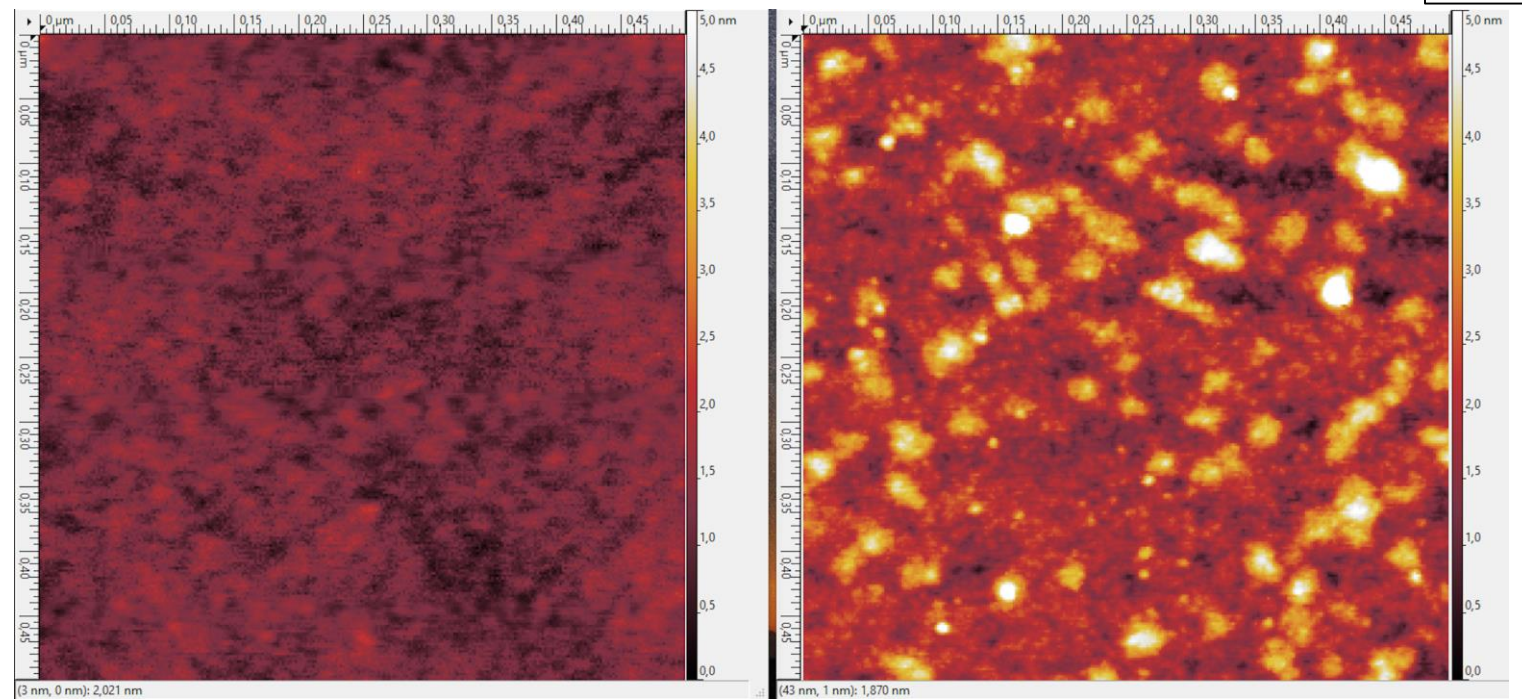


Pt Nanoparticle Deposition

- Larger capillary substrate distance needed → **New counter electrode**



AFM Topography Image



Substrate: Si, t = 1 min, P = 760 torr, $\Delta d = 10$ mm

→ **Achieved Pt nanoparticles: 3-10 nm, average = 4 nm Pt**

Summary & Next Steps

- Deposited diverse range of Pt nanostructures and morphologies
- Pressure and capillary substrate distance had greatest effect on Pt morphology
- Achieved average Pt nanoparticle size of 4 nm

- PtNi Alloy synthesis → Ni is readily available, less expensive than Pt
- Is PtNi catalytically active for ORR?
- Electrocatalytic testing underway

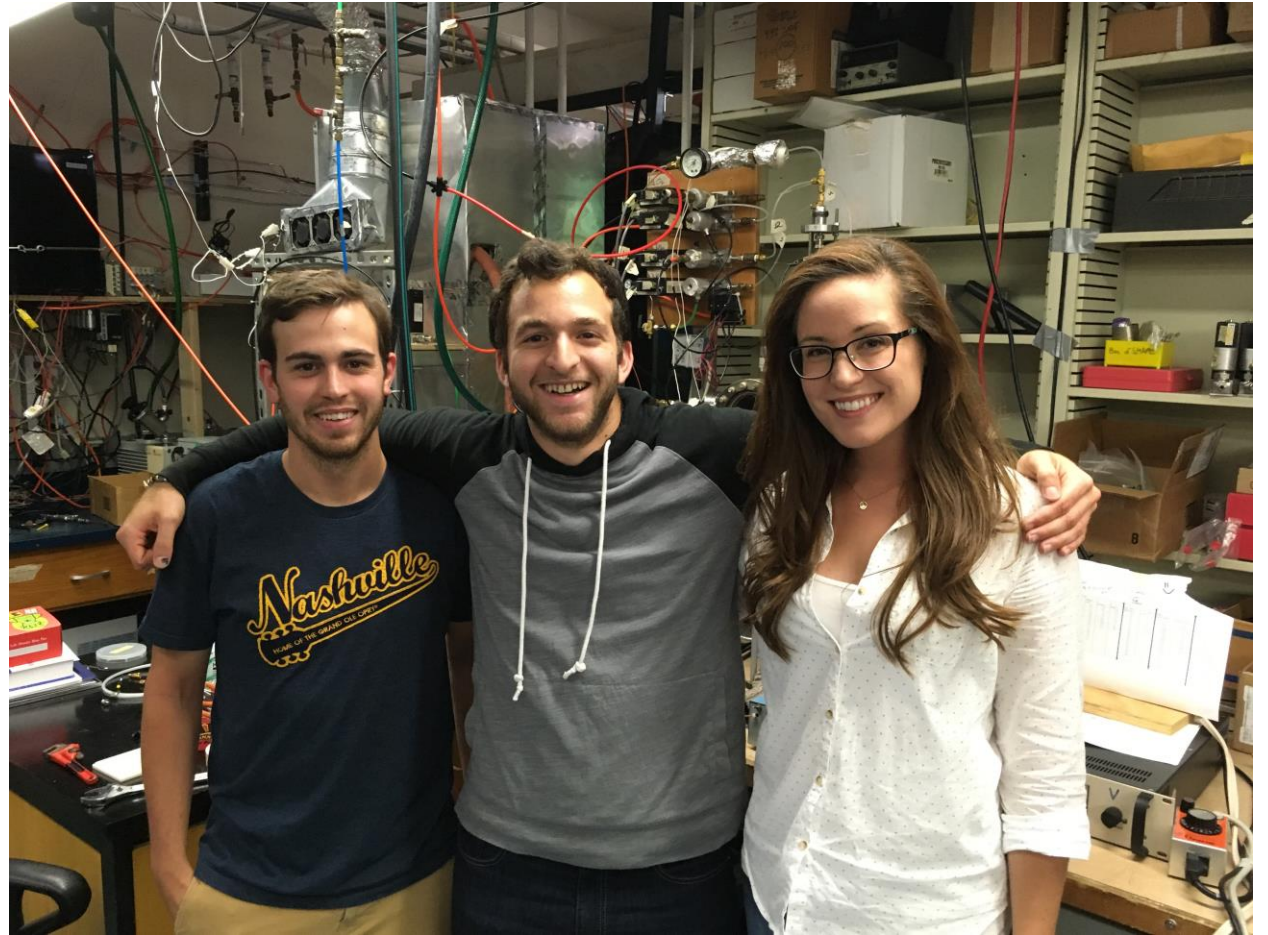
Acknowledgements



Professor Michael Gordon



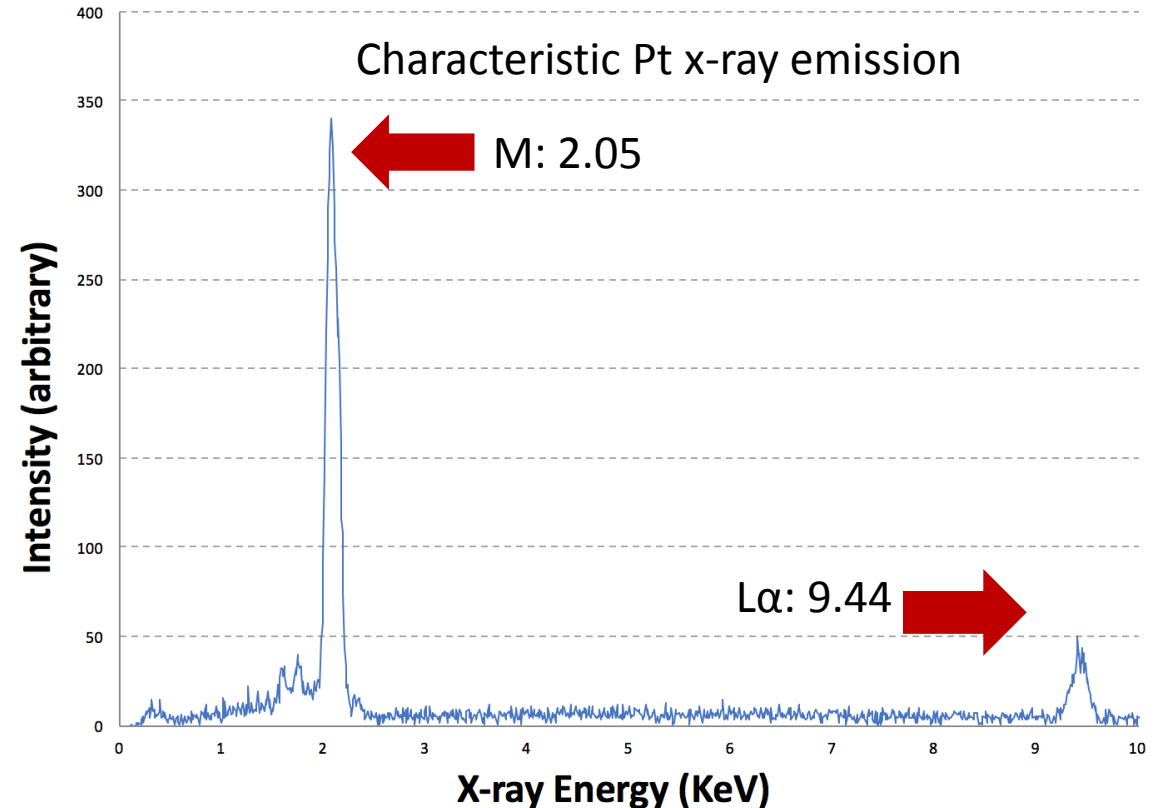
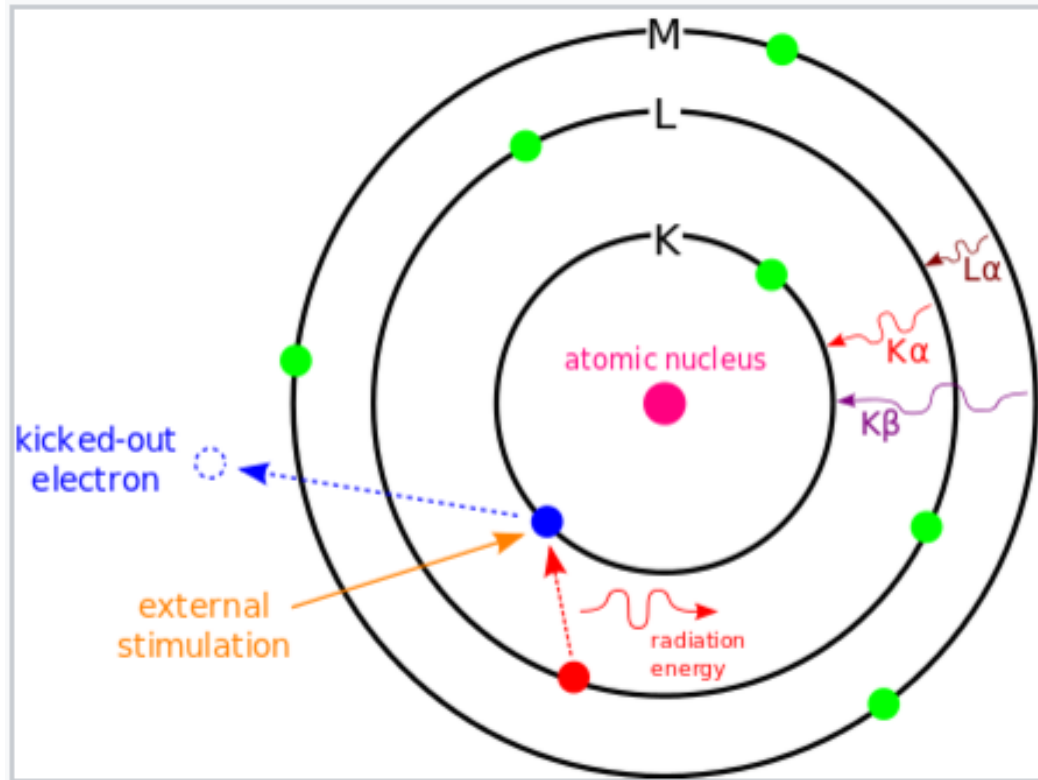
Funding



PhD Students: Joffrey Baneton and Katherine Mackie

Pt-film composition: EDX analysis

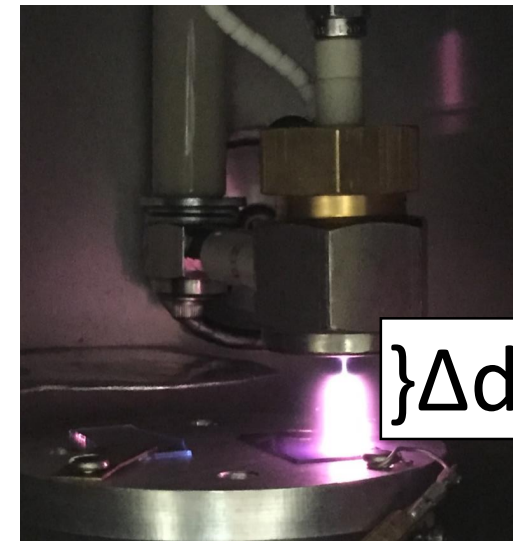
EDX = energy dispersive x-rays analysis



- Electron beam **kicks out core e⁻**, outer shell e⁻ fills, characteristic **x-ray released**
- Chemical elements present + relative abundance

Method to find Optimized Parameters for Nanoparticle Synthesis

- Design of experiments to test Pressure, O₂ addition, Pt-precursor temp. & capillary-substrate distance effects on resulting films
 - Pressure: 760 Torr
 - Deposition without 5% O₂ in plasma jet
 - Pt-precursor sublimation temperature: 40, 45 °C
- Film characterization
 - SEM: morphology, thickness
 - EDX (energy dispersive x-ray spectroscopy): film elemental composition
 - AFM: 30 sec, 1 min deposits to examine if nanoparticles are formed



Light Emission from Microplasma

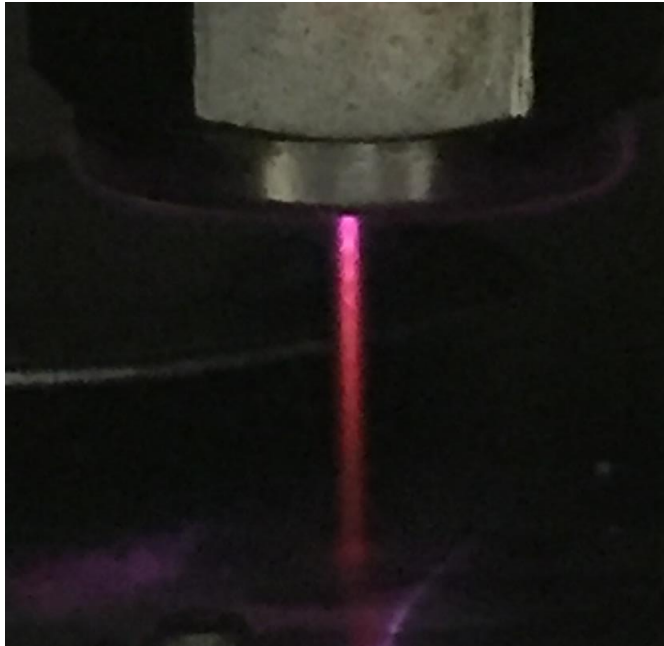
Low Pressure: $e^- + \text{Ar}^0 \rightarrow \text{Ar}^*$

Red Light Emission: $\text{Ar}^* \rightarrow \text{Ar}^0 + \text{red}$

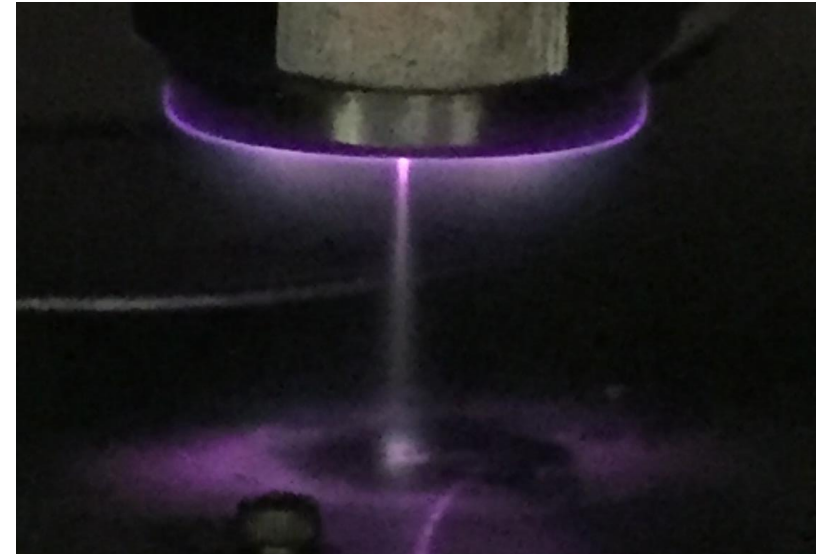
High Pressure: $e^- + \text{Ar}^0 \rightarrow \text{Ar}^{+*} + e^-$

Blue Light Emission $\text{Ar}^{+*} \rightarrow \text{Ar}^+ + \text{blue}$

P < 50 torr



P > 150 torr



- **Kinetic Energy** of electron ionizes Ar to $\text{Ar}^+ + e^- \rightarrow$ **Electron cascading** \rightarrow Plasma
- Excited States: $e^- + \text{Ar}^0 \rightarrow \text{Ar}^*$